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Gas-phase ion chemistry of silane with ethane and ethyne

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Abstract

Silane–ethane and silane–ethyne systems have been studied by ion trap mass spectrometry and the variation of the abundances, with reaction time, of the ions containing silicon and carbon together in 5:1, 1:1 and 1:5 mixtures, have been reported. The best ion yield, which increases with the total pressure, is observed for 1:1 silane–ethyne mixture. Reaction mechanisms and rate constants of the first nucleation processes have been determined. In SiH₄–C₂H₂ systems, the formation of ions containing new Si–C bonds occurs starting mainly from Si_mH_n⁺ ions in the first steps, whereas the Si_mC_nH_p⁺ cluster species further reacts with high efficiency in processes with ethyne. © 1999 Elsevier Science S.A. All rights reserved.

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1. Introduction

The interaction and reactivity of ions and molecules in gaseous systems containing silane and small saturated and unsaturated hydrocarbon molecules have been investigated by both experimental and theoretical methods [1-7]. This research allows the mechanisms of formation of chemical bonds between silicon and carbon in species identified in interstellar clouds [8,9] to be simulated, and in general, provides information on the intrinsic reactivity of ions in the absence of perturbations due to solvents or counterions [10-15]. Moreover, knowledge of the mechanisms and rate constants of ion-molecule reactions for the formation of hydrogenated clusters containing silicon and carbon is interesting from an applicative point of view. In fact, these ion species can be considered the charged precursors of amorphous silicon carbides. These are semiconducting materials with properties depending on the composition, and can be prepared by deposition from appropriate mixtures suitably activated [16,17].

In this paper we report results on: (i) the trends of abundances of ions containing new Si-C bonds, as a function of the partial pressures of the reagents, the

total pressure and reaction time; (ii) the mechanisms of chain propagation in silane–ethane and silane–ethyne systems, obtained by ion trap mass spectrometry. The rate constants of the main ion–molecule reactions are determined as well and compared with the collisional rate constants calculated by the Langevin theory [18]. A number of ion–molecule reactions observed in these systems have been studied previously in experiments carried out under rather different conditions [2,3].

2. Results and discussion

2.1. Silane-ethane mixtures

Variations of the total abundances of all the ions containing both silicon and carbon (mixed ions) for three $\text{SiH}_4-\text{C}_2\text{H}_6$ mixtures (5:1, 1:1 and 1:5 ratios of partial pressure of the reagents) are reported at the total pressure of 1.0×10^{-6} Torr, as a function of reaction time (Fig. 1). The best yield of all the mixed ions is given by the mixture with equal partial pressures, whilst an excess of C_2H_6 slightly lowers their relative abundances and an excess of SiH_4 strongly decreases them.

The reaction mechanisms have been studied through isolation steps of single ion species and identification of

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Fig. 1. Variation of total abundances with reaction time for silicon and carbon containing ions in $\rm SiH_4-C_2H_6$ mixtures at 1.0×10^{-6} Torr total pressure.

their charged products. In some cases, ionization of the two reagents gives isobaric primary ions, such as Si⁺ and C₂H₄⁺ at m/z 28; SiH⁺ and C₂H₅⁺ at m/z 29; SiH₂⁺ and C₂H₆⁺ at m/z 30. The reaction mechanisms starting from these species have been elucidated by experiments with the pulse valve and, therefore, with just one reagent in the trap during the ionization step.

The SiH_n⁺ (n = 0-3) primary ions of SiH₄ react with C₂H₆ to give the SiC₂H_n⁺ (n = 6, 7) ions. These products are formed by reaction of C₂H₆ with SiH₂⁺ and SiH₃⁺, respectively, with ejection of a hydrogen molecule, while a small contribution to the abundance of SiC₂H₆⁺ and SiC₂H₇⁺ is also given by addition of a molecule of ethane to Si⁺ and SiH⁺, without elimination of a neutral moiety. Moreover, Si⁺ gives SiCH₃⁺ and a methyl group, and SiH₃⁺ forms SiC₂H₅⁺ with elimination of two hydrogen molecules.

The $Si_2H_n^+$ ions, originated by self-condensation of SiH_4 , react with ethane too, yielding ions containing

silicon and carbon together. In particular, $Si_2H_4^+$ and $Si_2H_5^+$ give $Si_2C_2H_6^+$ and $Si_2C_2H_7^+$, respectively, and eliminate two hydrogen molecules. Peaks observed at m/z 84 and 85 are likely due to $Si_2C_2H_4^+$ and $Si_2C_2H_5^+$, respectively, which can originate in similar pathways, such as:

$$Si_2H_n^+ + C_2H_6 \rightarrow Si_2C_2H_{n+2}^+ + 2H_2$$
 (n = 2, 3) (1)

or from the isobaric SiC_2H_n^+ (n = 6, 7) ions, according to the following reaction:

$$SiC_2H_n^+ + SiH_4 \rightarrow Si_2C_2H_{n-2}^+ + 3H_2$$
 (n = 6, 7) (2)

However, the latter path is unlikely, as it involves the elimination of three neutral fragments. Moreover, a contribution from the $SiC_4H_8^+$ and $SiC_4H_9^+$ ions to the peaks at m/z 84 and 85 through the reaction:

$$SiC_2H_n^+ + C_2H_6 \rightarrow SiC_4H_{n+2}^+ + 2H_2$$
 (n = 6, 7) (3)

cannot be ruled out by experimental evidence, as both reactant and product ions of the reactions (1)–(3) have the same m/z value. Experiments using pulse valve or double isolation steps are not useful, as Si₂H₂⁺ and SiC₂H₆⁺ are both formed from Si⁺, just as Si₂H₃⁺ and SiC₂H₇⁺ are given by SiH⁺.

The primary $C_2H_n^+$ (n = 1-6) ions of C_2H_6 react with SiH₄ to give the SiH_n⁺ (n = 0-3) ion family and alkyl radicals or hydrocarbon molecules. A parallel reaction path forms the SiC₂H_n⁺ (n = 3-7) ions with elimination of one or two hydrogen molecules. In Table 1, the rate constants of the ion-molecule reactions of $C_2H_n^+$ (n =2, 3) with SiH₄ and of Si₂H₄⁺ with C₂H₆ are reported. The rate constants of other processes observed in this system could not be determined, either because they are too low to give reproducible results, or because the pressure is not constant in the experiments carried out with the pulse valve.

Table 1 also reports the reaction enthalpies, or their limits, of ion-molecule reactions involving species whose formation enthalpies are known from the literature [3,21-23]. The data show that all the processes observed are thermodynamically favoured.

Table 1

Rate constants for reactions of $C_2H_2^+$ and $C_2H_3^+$ ions with SiH_4 and of the $Si_2H_4^+$ ions with C_2H_6 in SiH_4 - C_2H_6 systems a

Reaction		k _{exp}	$\Sigma k_{\rm exp}$	k _L ^b	Efficiency °	ΔH^{o}_{298} d
$\overline{C_2H_2^+ + SiH_4}$	\rightarrow SiH ₂ ⁺ +C ₂ H ₄	2.6				-36.8
	\rightarrow SiH ₃ ⁺ + C ₂ H ₃	1.3				-24.9
	\rightarrow SiC ₂ H ₄ ⁺ + H ₂	1.1	5.0	12.85	0.39	<-50.4
$C_{2}H_{3}^{+}+SiH_{4}$	\rightarrow SiH ₃ ⁺ + C ₂ H ₄	3.2				-24.3
	\rightarrow SiC ₂ H ₅ ⁺ + H ₂	2.1	5.3	12.72	0.42	-43.6
$Si_2H_4^+ + C_2H_6$	\rightarrow Si ₂ C ₂ H ₆ ⁺ +2H ₂	2.6	2.6	11.05	0.24	

^a Rate constants are expressed as 10^{-10} cm³ molecule⁻¹ s⁻¹; experiments were run at 333 K.

^b Rate constants have been calculated according to the Langevin theory [18] taking the polarizability of SiH₄ from [19] and of C₂H₆ from [20]. ^c Efficiency has been calculated as the ratio $\Sigma k_{exp}/k_L$.

^d Enthalpies are expressed in kcal mol^{-1} and have been calculated with heats of formation taken from [3,21–23].



Fig. 2. Variation of total abundances with reaction time for silicon and carbon containing ions in $SiH_4-C_2H_2$ mixtures at 8.0×10^{-7} Torr total pressure.

2.2. Silane–ethyne mixtures

In Figs. 2 and 3 the variations of the abundances of all the ions containing both silicon and carbon are reported, as a function of reaction time, for three $SiH_4-C_2H_2$ systems (5:1, 1:1 and 1:5 ratios of partial pressure of the two reagents) at total pressures of 8.0×10^{-7} and 2.4×10^{-6} Torr, respectively. The increase of total pressure raises the yield of the $Si_mC_nH_p^+$ ions at any ratio of reagent partial pressures. At 2.4 × 10^{-6} Torr, the highest ion abundances are exhibited by



Fig. 3. Variation of total abundances with reaction time for silicon and carbon containing ions in $SiH_4-C_2H_2$ mixtures at 2.4×10^{-6} Torr total pressure.

the 1:1 mixture and the lowest ones by the mixture with an excess of ethyne.

A comparison of the trends of total ion abundances reported in Fig. 1 (silane–ethane) and Fig. 2 (silane– ethyne) shows a higher reactivity of ethyne with respect to ethane. This behaviour is not surprising basing on the presence of π electrons in ethyne, which enhance its reactivity with respect to ethane [10]. Moreover, in both systems the best yield of mixed ions is obtained in the 1:1 mixture, but an excess of ethyne reduces the abundances of mixed ions in the SiH₄–C₂H₂ mixture by a larger extent than an excess of ethane does in the SiH₄–C₂H₆ one.

The primary ions of silane SiH_n^+ (n = 0-3) react with C_2H_2 to originate the SiC₂H_n⁺ (n = 1, 3) ions and with SiH₄ to give the usual Si₂H_n⁺ (n = 2-5) ion species in self-condensation processes. Formation of $SiC_2H_n^+$ (n = 1, 3) occurs with good efficiencies from SiH⁺ and SiH_2^+ , respectively, as it can be seen from Table 2, where the rate constants of the main ion-molecule reactions of SiH_n^+ , $Si_2H_n^+$ and $Si_3H_5^+$ ions with C_2H_2 are shown. Moreover, formation of SiCH₃⁺ is also observed in the reaction of SiH+ with ethyne. The values of the self-condensation rate constants of SiH₄, obtained in these experiments, are also reported in Table 2 and are in good agreement with the data published in the literature [11,15,27]. The secondary $Si_2H_n^+$ (n = 2-5) ions are involved in self-condensation reactions to give the Si₃H_n⁺ (n = 4-7) species and react with ethyne to form the $Si_2CH_n^+$ (n = 1-3) and $Si_2C_2H_n^+$ (n = 2, 3, 5) ion families. As shown in Scheme 1, where the reaction pathways of SiH⁺ are reported as an example, the third reaction step starting from $Si_3H_5^+$ and neutral C₂H₂ leads to the Si₂CH⁺ ions, also formed from $Si_2H_3^+$, and to the most abundant $Si_3C_2H_3^+$ ions with elimination of two hydrogen molecules. These reactions show rather high rate constants. All the $Si_3H_n^+$ (n = 4-7) species exhibit a similar behaviour and the Si₃C₂H_n⁺ (n = 2-5) ions are important charged products containing silicon and carbon together. Reaction of $Si_3H_5^+$ with C_2H_2 also gives $Si_2C_2H_3^+$, from which $Si_2C_2H^+$ is formed in a successive step. This is an example of a general process encountered in this system, in which ethyne extracts two hydrogen atoms from a charged species to give a molecule of ethene.

The chain propagation proceeds further, mainly from ions containing only silicon and hydrogen. The Si₄H₇⁺ species, formed in self-condensation of Si₃H₅⁺, react in two successive steps leading to Si₄C₂H₅⁺ and Si₅C₂H₇⁺, respectively. The former product is obtained in the reaction with C₂H₂ and subsequent elimination of two H₂ molecules, and the latter in a second reaction with SiH₄ followed by elimination of one H₂ molecule. Furthermore, Si₄C₂H₅⁺ is involved in two parallel addition processes with both SiH₄ and C₂H₂, to give Si₅C₂H₉⁺ and Si₄C₄H₇⁺, respectively, without elimination of neu-

Table 2				
Rate constants for reactions of S	SiH_{n}^{+} , $Si_{2}H_{n}^{+}$ and $Si_{3}H_{5}^{+}$	ions with C ₂ H ₂ and	SiH ₄ in SiH ₄	-C ₂ H ₂ systems ^a

Reaction	k _{exp}	$\Sigma k_{\rm exp}$	k _L ^b	Efficiency ^c	ΔH^{o}_{298} d
$Si^+ + C_2H_2 \rightarrow SiC_2H^+ + H$	3.2	3.2	11.61	0.28	<-11.5
$+$ SiH ₄ \rightarrow Si ₂ H ₂ ⁺ $+$ H ₂	6.5	6.5	12.59	0.52	-19.1
$SiH^+ + C_2H_2 \rightarrow SiC_2H^+ + H_2$	8.4	8.4	11.51	0.73	<-40
$+$ SiH ₄ \rightarrow Si ₂ H ₃ ⁺ $+$ H ₂	7.8	7.8	12.47	0.63	-15.5
$SiH_2^+ + C_2H_2 \rightarrow Si^+ + C_2H_4$	2.0				-21
\rightarrow SiC ₂ H ₃ ⁺ + H	7.5	9.5	11.41	0.83	-26.5
$+$ SiH ₄ \rightarrow SiH ₃ ⁺ $+$ SiH ₃	5.5				1.5
\rightarrow Si ₂ H ₄ ⁺ + H ₂	7.3	12.8	12.36	1.04	-16.1
$SiH_3^+ + C_2H_2 \rightarrow SiH^+ + C_2H_4$	2.3				-5.6
\rightarrow SiC ₂ H ₃ ⁺ + H ₂	0.83	3.1	11.32	0.28	- 39.5
$+$ SiH ₄ \rightarrow Si ₂ H ₅ ⁺ $+$ H ₂	0.5	0.50	12.26	0.04	-16.1
$Si_2H_2^+ + C_2H_2 \rightarrow Si_2CH^+ + CH_3$	6.0				
\rightarrow Si ₂ C ₂ H ₂ ⁺ + H ₂	0.42				
\rightarrow Si ₂ C ₂ H ₃ ⁺ + H	0.79	7.2	10.05	0.72	
$+$ SiH ₄ \rightarrow Si ₃ H ₄ ⁺ $+$ H ₂	0.35	0.35	10.71	0.03	<-29
$Si_2H_3^+ + C_2H_2 \rightarrow Si_2CH^+ + CH_4$	0.86				
\rightarrow Si ₂ CH ₂ ⁺ + CH ₃	1.2				+13.3
\rightarrow Si ₂ C ₂ H ₃ ⁺ + H ₂	2.4	4.5	10.03	0.45	
$+$ SiH ₄ \rightarrow Si ₃ H ₅ ⁺ $+$ H ₂	3.4	3.4	10.68	0.32	<-34
$Si_2H_4^+ + C_2H_2 \rightarrow SiC_2H_3^+ + SiH_3$	0.43				-22
\rightarrow Si ₂ H ₂ ⁺ + C ₂ H ₄	3.9				-24
\rightarrow Si ₂ CH ₃ ⁺ + CH ₃	0.91				-29.7
\rightarrow Si ₂ C ₂ H ₄ ⁺ + H ₂	1.4				
\rightarrow Si ₂ C ₂ H ₅ ⁺ + H	1.3	7.9	10.01	0.79	<+5.6
$+$ SiH ₄ \rightarrow Si ₃ H ₆ ⁺ $+$ H ₂	0.2	0.20	10.65	0.02	<+3
$Si_2H_5^+ + C_2H_2 \rightarrow SiC_2H_3^+ + SiH_4$	0.24				-23.5
\rightarrow Si ₂ H ₃ ⁺ + C ₂ H ₄	2.9				-5
\rightarrow Si ₂ C ₂ H ₅ ⁺ + H ₂	5.1	8.2	9.98	0.83	
$+$ SiH ₄ \rightarrow Si ₃ H ₇ ⁺ $+$ H ₂	0.62	0.62	10.62	0.06	
$Si_3H_5^+ + C_2H_2 \rightarrow Si_2CH^+ + SiCH_6$	2.5				
\rightarrow Si ₃ H ₃ ⁺ + C ₂ H ₄	1.0				
\rightarrow Si ₃ C ₂ H ₃ ⁺ +2H ₂	4.0				
\rightarrow Si ₂ C ₂ H ₃ ⁺ + SiH ₄	0.53	8.0	8.12	0.99	
$+$ SiH ₄ \rightarrow Si ₄ H ₇ ⁺ $+$ H ₂	4.0	4.0	10.03	0.40	

^a Rate constants are expressed as 10^{-10} cm³ molecule⁻¹ s⁻¹; experiments were run at 333 K.

^b Rate constants have been calculated according to the Langevin theory [18] taking polarizability of C_2H_2 from [20] and of SiH₄ from [19]. ^c Efficiency has been calculated as the ratio $\Sigma k_{exp}/k_L$.

^d Enthalpies are expressed in kcal mol⁻¹ and have been calculated with heats of formation taken from [3,21–26].

tral species. A similar reaction pattern is displayed by $Si_5C_2H_7^+$, which gives $Si_6C_2H_{11}^+$ and $Si_5C_4H_9^+$. Again no neutral species are eliminated in these processes.

The primary ions of C_2H_2 , $C_2H_n^+$ (n = 0-2), react with silane, leading to the SiH_n^+ (n = 0-3) and SiC₂H_n^+ (n = 3-5) ion families. Both C_2H^+ and $C_2H_2^+$ ions show high total efficiencies and relatively high rate constants for the reaction channels leading to silicon and carbon containing ions (see Table 3). Selfcondensation of ethyne gives the $C_4H_2^+$ and $C_4H_3^+$ species, which also lead to ions containing new Si–C bonds, with formula SiC₂H_n^+ (n = 1-5) and SiC₄H₅⁺. Very high efficiencies are obtained for reactions starting from $C_4H_2^+$ ions. The formation of SiCH₃⁺ is observed too, which occurs either from reaction of SiH₄ with $C_2H_2^+$ and subsequent elimination of a methyl group, or with $C_4H_3^+$, followed by elimination of C_3H_4 .

Formation of clusters of increasing size takes place also through reaction channels involving ion species containing silicon and carbon reacting with both the neutral reagents, as can be observed in Scheme 1 for the species originated by SiH⁺. In particular, the $Si_2CH_n^+$ (n = 1-3) ions react with SiH_4 and, after elimination of H₂, give the Si₃CH⁺_n (n = 1, 3-5) family, which further reacts with C_2H_2 leading to $Si_3C_3H_n^+$ (n = 3-5). The SiC₂H_n⁺ (n = 3-5) ions react with both silane and ethyne to give the Si₂C₂H_n⁺ (n = 5-7) and $Si_2C_4H_n^+$ (n = 5, 7) products, respectively. By contrast, under the experimental conditions used, SiC₂H⁺ does not react any further with appreciable rate constant. Finally, parallel reactions of $Si_3C_2H_n^+$ (n = 3-5) with silane and ethyne take place, and the Si₄C₂H⁺_n (n =5, 7) and Si₂C₃H_n⁺ (n = 1, 3) families are formed.

A comparison of the collisional rate constants, calculated on the basis of the Langevin theory, with the



a reaction with silane b reaction with ethyne

Scheme 1. Reaction pathways of SiH^+ in $SiH_4-C_2H_2$ mixtures.

experimental rate constants of reaction of $SiC_2H_n^+$, $Si_2C_2H_n^+$, and $SiC_4H_5^+$ ions with C_2H_2 and SiH_4 , reported in Table 4, indicates rather high efficiencies for reactions in which C_2H_2 is the neutral reagent, whilst

efficiencies are very low when a SiH₄ molecule is involved in the processes. In Tables 2–4 the reaction enthalpies for all the ion-molecule reactions of species whose formation enthalpies are known from the literature are also reported [3,21–28]. The negative ΔH_{298}° values for most of them confirm that these processes are thermodynamically favoured.

3. Conclusions

The dependence of the yield of ions containing both silicon and carbon on the ratio of the partial pressures of reagents in silane-ethyne mixtures (Figs. 2 and 3) suggests an involvement, to a similar extent, of both silane and ethyne in their formation. In particular, the first steps of the chain propagation consist mainly of reactions of $Si_m H_n^+$ ions, given by self-condensation of SiH₄, with ethyne. This is in agreement with the increase of the abundances of $Si_m C_n H_p^+$ species with the partial pressure of SiH₄. A similarly high contribution to the abundances of mixed ions is to be ascribed to ethyne, because the $Si_m C_n H_p^+$ ions are involved in the chain propagation with high efficiency when the neutral molecule is ethyne. A further influence of ethyne on the yield of mixed ions is evident from Table 3, where processes of formation of the SiH_n^+ family from both $C_2H_n^+$ and $C_4H_2^+$ ions with SiH₄ show high efficiencies.

Table 3 Rate constants for reactions of $C_2H_n^+$ and $C_4H_n^+$ ions with SiH_4 in $SiH_4-C_2H_2$ systems "

Reaction	k_{exp}	$\Sigma k_{\rm exp}$	k _⊥ ^b	Efficiency ^c	ΔH^{o}_{298} d
$\overline{C_2H^+ + SiH_4 \rightarrow Si^+ + C_2H_5}$	2.4				-87.9
\rightarrow SiH ⁺ + C ₂ H ₄	0.68				-127
\rightarrow SiH ₂ ⁺ + C ₂ H ₃	1.3				-73.5
\rightarrow SiH ₃ ⁺ + C ₂ H ₂	1.2				-121.4
\rightarrow SiC ₂ H ₃ ⁺ + H ₂	5.7	11.3	12.99	0.87	-161
$C_2H_2^+ + SiH_4 \rightarrow Si^+ + C_2H_6$	1.9				-48.4
\rightarrow SiH ₂ ⁺ + C ₂ H ₄	2.9				-36.8
\rightarrow SiH ₃ ⁺ + C ₂ H ₃	1.1				-24.9
\rightarrow SiCH ₃ ⁺ + CH ₃	1.7				-55.6
\rightarrow SiC ₂ H ₃ ⁺ + H + H ₂	2.7				-21.3
\rightarrow SiC ₂ H ₄ ⁺ + H ₂	1.0				<-48.4
\rightarrow SiC ₂ H ₅ ⁺ + H	3.1	14.4	12.85	1.12	-43
$C_4H_2^+ + SiH_4 \rightarrow SiC_2H^+ + C_2H_5$	0.36				<-32
\rightarrow SiC ₂ H ₂ ⁺ + C ₂ H ₄	2.1				<+14.5
\rightarrow SiC ₂ H ₃ ⁺ + C ₂ H ₃	0.76				-32.6
\rightarrow SiC ₂ H ₄ ⁺ +C ₂ H ₂	1.8				<-16.5
\rightarrow SiC ₃ H ₃ ⁺ + CH ₃	3.7				-33.2
\rightarrow SiC ₄ H ⁺ ₅ + H	2.0	10.7	11.02	0.97	<-19.9
$C_4H_3^+ + SiH_4 \rightarrow SiCH_3^+ + C_3H_4$	0.45				-19.4
\rightarrow SiC ₂ H ₃ ⁺ +C ₂ H ₄	0.72				-34.5
\rightarrow SiC ₂ H ₅ ⁺ + C ₂ H ₂	1.9	3.1	10.97	0.28	-14.2

^a Rate constants are expressed as 10⁻¹⁰ cm³ molecule⁻¹ s⁻¹; experiments were run at 333 K.

^b Rate constants have been calculated according to the Langevin theory [18] taking polarizability of SiH₄ from [19].

 $^{\rm c}$ Efficiency has been calculated as the ratio $\Sigma k_{\rm exp}/k_{\rm L}.$

^d Enthalpies are expressed in kcal mol⁻¹ and have been calculated with heats of formation taken from [3,21–23,28].

Table 4					
Rate constants of reactions of	of $SiC_2H_n^+$, $Si_2C_2H_n^+$	and SiC ₄ H ₅ ⁺ ions	s with SiH ₄ and	C ₂ H ₂ in SiH ₄ -C ₂ H ₂	systems ^a

Reaction	k _{exp}	$\Sigma k_{\rm exp}$	k _L ь	Efficiency ^c	ΔH°_{298} d
$\overline{\operatorname{SiC}_2\operatorname{H}_3^+ + \operatorname{C}_2\operatorname{H}_2 \rightarrow \operatorname{SiC}_2\operatorname{H}^+ + \operatorname{C}_2\operatorname{H}_4}$	3.1	3.1	10.15	0.31	<-6
$+$ SiH ₄ \rightarrow Si ₂ C ₂ H ₅ ⁺ +H ₂	0.23	0.23	10.81	0.02	
$SiC_2H_4^+ + C_2H_2 \rightarrow SiC_2H_2^+ + C_2H_4$	3.5				
\rightarrow SiC ₃ H ₃ ⁺ +CH ₃	1.1				>-14.7
\rightarrow SiC ₄ H ₅ ⁺ + H	0.40	5.0	10.12	0.49	
$+$ SiH ₄ \rightarrow Si ₂ H ₄ $^+$ $+$ C ₂ H ₄	0.57				>-2.5
\rightarrow Si ₂ C ₂ H ₆ ⁺ + H ₂	0.56	1.1	10.78	0.10	
$SiC_2H_5^+ + C_2H_2 \rightarrow SiC_2H_3^+ + C_2H_4$	2.9				-2.3
\rightarrow SiC ₄ H ⁺ ₅ + H ₂	2.5	5.4	10.09	0.54	<-8.8
$+$ SiH ₄ \rightarrow Si ₂ C ₂ H ₇ ⁺ $+$ H ₂	0.20	0.20	10.75	0.02	
$SiC_4H_5^+ + C_2H_2 \rightarrow SiC_6H_5^+ + H_2$	1.6				
\rightarrow SiC ₆ H ⁺ ₇	0.37	2.0	9.61	0.21	
$+$ SiH ₄ \rightarrow Si ₂ C ₂ H ₅ ⁺ $+$ C ₂ H ₄	0.56				
\rightarrow Si ₂ C ₄ H ₇ ⁺ + H ₂	0.41				
\rightarrow Si ₂ C ₄ H ₉ ⁺	1.0	2.0	10.16	0.20	
$Si_2C_2H_3^+ + C_2H_2 \rightarrow Si_2CH^+ + C_3H_4$	0.23				
\rightarrow Si ₂ C ₂ H ⁺ +C ₂ H ₄	1.6	1.8	9.59	0.19	
$+$ SiH ₄ \rightarrow Si ₃ C ₂ H ₅ ⁺ $+$ H ₂	0.27	0.27	10.12	0.03	
$Si_2C_2H_4^+ + C_2H_2 \rightarrow Si_2C_2H_2^+ + C_2H_4$	1.3				
\rightarrow Si ₂ C ₃ H ⁺ ₅ + CH	1.7				
\rightarrow Si ₂ C ₄ H ⁺ ₅ + H	1.3	4.3	9.57	0.45	
$+$ SiH ₄ \rightarrow Si ₃ C ₂ H ₆ ⁺ $+$ H ₂	0.41	0.41	10.10	0.04	
$Si_2C_2H_5^+ + C_2H_2 \rightarrow Si_2C_2H_3^+ + C_2H_4$	1.1				
\rightarrow Si ₂ C ₃ H ₄ ⁺ + CH ₃	0.10				
\rightarrow Si ₂ C ₄ H ⁺ ₅ + H ₂	0.78	2.0	9.56	0.21	
$+$ SiH ₄ \rightarrow Si ₃ C ₂ H ₇ ⁺ $+$ H ₂	0.49	0.49	10.09	0.05	

^a Rate constants are expressed as 10⁻¹⁰ cm³ molecule⁻¹ s⁻¹; experiments were run at 333 K.

^b Rate constants have been calculated according to the Langevin theory [18] taking the polarizability of SiH₄ from [19] and of C₂H₂ from [20]. ^c Efficiency has been calculated as the ratio $\Sigma k_{exp}/k_{L}$.

^d Enthalpies are expressed in kcal mol⁻¹ and have been calculated with heats of formation taken from [3,23–25].

4. Experimental

All the experiments were run on an ITMS Finnigan mass spectrometer. Silane, ethane and ethyne were obtained commercially in high purity. Each of them was introduced into a flask, containing anhydrous sodium sulfate as drier, which was connected to one line of the gas inlet system of the instrument. Helium, used as buffer gas, was supplied at an extra-high purity and used without further purification. A Bayard Alpert ionization gauge was used to measure pressure. All read pressures were corrected for the relative sensitivity of the ion gauge with respect to different gases, 1.70 for SiH₄ [29], 2.39 for C₂H₆ [29] and 1.53 for C₂H₂ [29], and for a calibration factor, calculated as reported previously [11], to obtain the real pressure in the trap. Helium was admitted to the trap at a pressure of about 4×10^{-4} Torr. The temperature of the trap was maintained at 333 K, at which other related systems have been investigated. In order to prevent side reactions with the water background, the manifold and the lines for the introduction of reagent gases and helium were frequently baked-up. In all the experiments, ions were detected in the 10-300 u mass range. In these experiments, the scan modes used both to study the overall ion reactivity, as a function of reaction time, and to determine reaction mechanisms and rate constants have been described in detail previously, as well as the procedures for calculations [11,12].

In kinetic experiments, isolation of ions at a specific m/z value was obtained by use of d.c. voltages and by resonance ejection. In the latter isolation method, no field is directly applied on the selected ion species and, therefore, the ions should contain a lower excitation energy. The rate constants obtained by these two different isolation procedures are very similar and have an uncertainty that falls within 20%. This is in agreement with the hypothesis that the reactant ions undergo a number of collisions sufficient to eliminate most of their excitation energy. The single-exponential decays observed in the kinetic experiments are in agreement with this hypothesis. As an example, Fig. 4 reports the logarithmic plot of the decrease in relative abundance of the SiH+ species with reaction time in a silaneethyne mixture. The correlation coefficient shows a high curve fitting of the experimental points, which is similar to those obtained for all the other ions considered.

In all the experiments, ionization was obtained by electrons at about 35 eV for times in the range 1-10



Fig. 4. Plot of ln[SiH⁺] versus reaction time for a SiH₄ $(3.9 \times 10^{-7} \text{ Torr})-C_2H_2$ $(3.6 \times 10^{-7} \text{ Torr})$ mixture.

ms. In experiments without selective storage of ions, ionization is followed by a reaction time that ranges from 0 to 1 s, without application of any potential to the trap. Acquisition of ion signals closes the experiment. When isolation of an ion species is performed, after the ionization event, a reaction time can follow in order to maximize the abundances of the ions under examination. Isolation of the selected ions, storage in the trap for convenient reaction times and acquisition are the successive events.

In some cases, when signals are due to two isobaric species, such as Si⁺ and C₂H₄⁺ (m/z 28) in the silane– ethane mixture, experiments were performed by pulsing one of the reagent gases. In this way, one gas is always present in the trap and the other reagent is pulsed into the trap only after the ionization step. Ion–molecule reactions occur between a single ion species (Si⁺ or C₂H₄⁺) and both neutrals and the reaction mechanisms of each of the isobaric ions can be determined. A General Valve Corporation Iota One pulsed valve was used [30]. The pressure of the pulsed gas behind the valve is previously set at 5.0×10^{-7} Torr by means of a by-pass channel and the valve opening time is 0.200 ms.

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